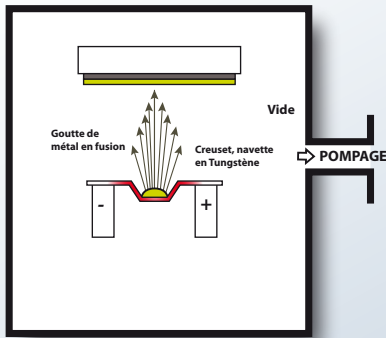


# Techniques de dépôts de films minces

## → Evaporation *Evaporator*

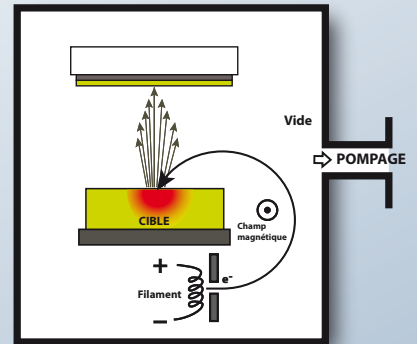


Aluminium, Or, Chrome

## → Evaporation par canon à électrons *Electron gun evaporator*



Univex 350



Or, Platine, Palladium  
Titane, Chrome

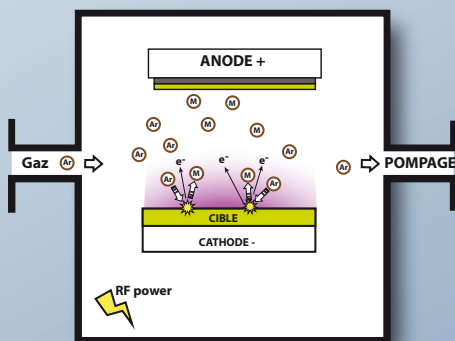
## → Pulvérisation cathodique *Sputtering*



Univex 450



Alcatel SCM 600

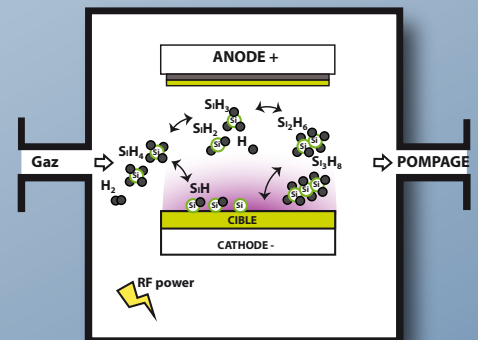


Or, Titane, Chrome  
Platine,  $Al_2O_3$ ,  $SiO_2$ ,  
Au/ge/Ni, Au/Zn, Au/Sn

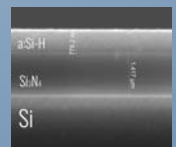
## → PECVD : Dépôt Chimique en phase vapeur assisté par plasma *Plasma enhanced chemical vapour deposition*



Corial D250



$Si_3N_4$ ,  $SiO_2$ , a:SiH



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